

Tystar Furnaces

Overview

This section describes the Tystar LPCVD tube stack. The stack consists of 6 tubes for Nitride, Poly Si, Doped Poly Si, Doped Anneal, General Anneal and Oxidation. Each tube is considered a separate tool in LMACS.

LMACS Name	LPCVD Nitride Deposition
	LPCVD PolySi Deposition
	LPCVD Boron Doped PolySi Deposition
	Tystar Doped Anneal
	Tystar General Anneal
	Tystar Oxidation
Process Area	DEPOSITION
Model	Tytan Mini Series
Vendor	Tystar
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LPCVD Tube Configuration & Chemistry

 The LPCVD Stack contains 3 furnaces, each configured for unique processing, with different chemistry. Details of the configuration are listed below.

Tube Number	Process Name	Chemistry
1	EMPTY	N/A
2	Nitride	DCS, NH ₃
3	Poly Si	(100%) SiH ₄
4	Boron Doped Poly Si	(100%) SiH ₄ , (3%) BCl ₃
5	Doped Anneal	N ₂
6	General Anneal	N ₂
7	Oxidation	Oxygen, H ₂ O
8	EMPTY	N/A

Related Documents

- [Tystar Furnaces](#) (Equipment)
 - [tystar](#)
 - [lpcvd](#)
 - [\\$labeltext](#)
- [Tystar Tubes 2, 3, and 4 \(LPCVD\) HA](#) (Equipment)
 - [hazard-assessment](#)
 - [deposition](#)
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- lpcvd
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 - tube4
- Tystar LPCVD - Tube 4 (doped Poly Si) (Equipment)
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- Tystar LPCVD - Tube 3 (Poly Si) (Equipment)
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- Tystar LPCVD - Tube 2 (Nitride) (Equipment)
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- Tystar LPCVD SOP (Equipment)
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- LPCVD Tube 4 Process Record - Results (Equipment)
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